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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Hiroyuki YANO, et al.

SERIAL NO: 09/531,163

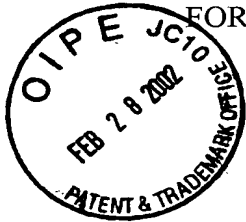
FILED: MARCH 17, 2000

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: EXAMINER: D. DEO

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: GROUP ART UNIT: 1765



FOR: AQUEOUS DISPERSION, AQUEOUS
DISPERSION FOR CHEMICAL
MECHANICAL POLISHING USED
FOR MANUFACTURE OF
SEMICONDUCTOR DEVICES,
METHOD FOR MANUFACTURE OF
SEMICONDUCTOR DEVICES, AND
METHOD FOR FORMATION OF
EMBEDDED WIRING

RECEIVED

MAR 04 2002

TC 1700

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Responsive to the Office Action of December 4, 2001, Applicants respectfully request reconsideration in view of the following remarks.

IN THE CLAIMS

Please cancel claims 61-75.

REMARKS

Applicants thank Examiner Deo for the helpful and courteous interview of December 20, 2001 with Applicants' U.S. representative. During the interview the unobviousness of the presently claimed invention was discussed. It was noted that the molecular weight of the